

U.S. Department of Commerce, Patent and Trademark Office		Docket No.	Serial No.
(PTO Form 1449 modified)		8377/ETCH/SILICON	10/666,317
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>		Applicant Mui, et al.	Confirmation No.: 7907
Use several sheets if necessary)		Filing Date	Group
Examiner		September 19, 2003	1765

**U.S. Patent Documents**

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
EC	A1	4,767,496	08/30/1988	Hieber	156	627	
	A2	5,798,529	08/25/1998	Wagner	250	492.2	
	A3	5,926,690	07/20/1999	Toprac et al.	438	17	
	A4	5,948,203	09/07/1999	Wang	156	345	
	A5	6,004,706	12/21/1999	Ausschnitt et al.	430	30	
	A6	6,027,842	02/22/2000	Ausschnitt et al.	430	30	
	A7	6,161,054	12/12/2000	Rosenthal et al.	700	121	
	A8	6,245,581	06/12/2001	Bonser et al.	438	8	
	A9	6,424,417	07/23/2002	Cohen et al.	356	388	
	A10	6,486,492	11/26/2002	Su	257	48	
	A11	2002/0171828	11/21/2002	Cohen et al.	356	328	07/01/2002

**Foreign Patent Documents**

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
	B1						<input type="checkbox"/>	<input type="checkbox"/>
	B2						<input type="checkbox"/>	<input type="checkbox"/>

**OTHER ART**

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
EC	C1	Lee, et al., "Analysis of Reflectometry and Ellipsometry Data from Patterned Structures," Characterization and Metrology for UCSI Technology: 1998 International Conference, Seiler, et al., eds., pg 331-335
	C2	Raymond, "Angle-resolved scatterometry for semiconductor manufacture," Micro lithography World, Winter 2000.
	C3	Toprac, A., "AMD's Advanced Process Control of Ply-Gate Critical Dimension," Proc. SPIE Vol 3882, pg 62-65, Sept, 1999.
	C4	Yang, et al., "Line-profile and Critical Dimension Measurements Using a Normal Incidence Optical Metrology System," Proceedings of SPIE Vol. 4689, March 2002.
Examiner	Date Considered 5/13/05	

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.